Study on the Reaction of $CH₂$ with H₂ at High Temperature

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ABSTRACT: Thermal decomposition of $CH₂I₂$ [sequential C−I bond fission processes, $CH_2I_2 + Ar \rightarrow CH_2I + I + Ar$ (1a) and $CH_2I + Ar \rightarrow {^3}CH_2 + I + Ar (1b)$, and the reactions of ${}^3CH_2 +$ $H_2 \rightarrow CH_3 + H(2)$ and ¹CH₂ + H₂ \rightarrow CH₃ + H (3) have been studied by using atomic resonance absorption spectrometry (ARAS) of I and H atoms behind reflected shock waves. Highly diluted CH₂I₂ (0.1–0.4 ppm) with/without excess H₂ (300 ppm) in Ar has been used so that the effect of the secondary reactions can be minimized. From the quantitative measurement of I atoms in the 0.1 ppm $CH₂I₂ + Ar$ mixture over 1550–2010 K, it is confirmed that two-step sequential C−I bond fission processes of $CH₂I₂$, (1a) and (1b), dominate over other product channels. The

decomposition step (1b) is confirmed to be the rate determining process to produce 3CH_2 [and the least-squares analysis of the](http://pubs.acs.org/action/showImage?doi=10.1021/jp211849h&iName=master.img-000.jpg&w=227&h=118) measured rate gives, $\ln(k_{1b}/cm^3$ molecule⁻¹ s⁻¹) = -(17.28 ± 0.79) - (30.17 ± 1.40) × 10³/T. By utilizing this result, we examine reactions 2 and 3 by monitoring evolution of H atoms in the 0.2–0.4 ppm CH₂I₂ + 300 ppm H₂ mixtures over 1850– 2040 K. By using a theoretical result on k_2 (Lu, K. W.; Matsui, H.; Huang, C.-L.; Raghunath, P.; Wang, N.-S.; Lin, M. C. J. Phys. *Chem.* A 2010, 114, 5493), we determine the rate for (3) as k_3 /cm³ molecule⁻¹ s⁻¹ = (1.27 ± 0.36) × 10⁻¹⁰. The upper limit of k_3 (k_{3max}) is also evaluated by assuming $k_2 = 0$, i.e., k_{3max}/cm^3 molecule⁻¹ s⁻¹ = (2.26 ± 0.59) × 10⁻¹⁰. The present experimental results on k_3 and k_{3max} is found to agree very well with the previous frequency modulation spectroscopy study (Friedrichs, G.; Wagner, H. G. Z. Phys. Chem. **2001**, 215, 1601); i.e., the importance of the contribution of ¹CH₂ in the reaction of CH₂ with H₂ at elevated temperature range is reconfirmed.

1. INTRODUCTION

The methylene radical, CH_2 $(\tilde{X}^3B_1$ and \tilde{a}^1A_1 , represented as \tilde{a}^3CH and 1CH representively) is reparded as an important CH_2 and ${}^{1}CH_2$, respectively), is regarded as an important reaction intermediate in hydrocarbon combustion. In the standard combustion conditions, $CH₂$ radicals are supplied mostly in the secondary reactions such as CH₃ + OH \rightarrow ¹CH₂ + H_2O and sequential collisional quenching ${}^1CH_2 + M \rightarrow {}^3CH_2 +$ $M_i^{1–3}$ therefore, the higher the concentration of fuel species, the more important the role of CH₂. Also, it is indicated that 1 CH₂ is a [direc](#page-5-0)t product in the thermal decomposition of $CH₃OH^{2,3}$ In this case, $CH₂$ radical plays an important role in the initial stage of the chain branching processes even if the concentrati[on](#page-5-0) of $CH₃OH$ is low.

Detection of $CH₂$ radical has been tried by using various techniques (LMR spectrometers, mass spectrometers, infrared diode laser absorption for ³CH₂, and LIF and others for 1 CH), a large amount of information about the rate con- $^{1}CH_{2}$); a large amount of information about the rate constants and reaction mechanism of $CH₂$ radical have been accumulated at low temperature range.⁴⁻²¹ Also, shock tube works combined with ARAS (atomic resonance absorption spectrometry) and the frequency m[odula](#page-5-0)tion spectroscopy have been conducted to explore the $CH₂$ reactions above 1000 K.^{22−25,36}

The main issue of this study is to obtain reliable kinetic informa[tion by](#page-5-0) monitoring evolution of H atoms produced in the reaction of $CH_2 + H_2$ at high temperature range. Highly sensitive detection of H atoms $(1 \times 10^{11}/\text{cm}^3)$ of this study

would be efficient to reduce the effects of the side reactions. In addition, excellent reproducibility of the experimental condition in this shock tube system enables comparative measurement to confirm the concentration of the minor component in the sample mixture, as well as to examine the contributions of the background H atoms.

In most of the previous experimental studies, photolysis or thermal decomposition of $CH₂CO$ has been used as a source of supplying CH_2 . As CH_2CO is relatively stable below 2000 K, it is also the issue of the present study to search a clean source of producing $CH₂$ radical at lower temperature range. Therefore, this study is divided into two main experimental parts. In the first part, evolution of I atoms has been monitored by using VUV absorption at 178.3 nm in the mixture of 0.1 ppm $CH₂I₂$ + Ar over 1550−2010 K to examine the thermal decomposition process (1) , i.e.,

$$
CH_2I_2 + Ar \rightarrow CH_2I + I + Ar \tag{1a}
$$

and

$$
CH2I + Ar \rightarrow {}3CH2 + I + Ar
$$
 (1b)

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By using the result of thermal decomposition of $CH₂I₂$, we have examined the reactions

$$
{}^{3}\text{CH}_{2} + \text{H}_{2} \rightarrow \text{CH}_{3} + \text{H}
$$
 (2)

and

$$
{}^{1}CH_{2} + H_{2} \rightarrow CH_{3} + H
$$
 (3)

by monitoring H atoms. Even though ${}^{3}CH_{2}$ is expected to be the main products in (1b), it is important to take into account (3) at elevated temperature condition, as the collisional energy transfer between ${}^{1}CH_{2}$ an[d](#page-0-0) ${}^{3}CH_{2}$, (4) is very fast:

$$
{}^{1}CH_{2} + M = {}^{3}CH_{2} + M
$$
 (4)

2. EXPERIMENTAL SYSTEM

Experimental study has been conducted behind reflected shock waves in a diaphragmless shock tube apparatus (length 5.9 m and i.d. 7.6 cm). Details of experiments were described in previous studies.^{26,27} An atomic resonance absorption spectrometry (ARAS) detection system has been used for the measurements o[f tem](#page-5-0)poral profiles of [I] and [H]; i.e., the resonant atomic absorption of I atoms at 178.3 nm (corresponding to transition ${}^{2}P_{1,3/2} - {}^{2}P_{0,3/2}$) and that of H atoms at 121.6 nm are monitored by a microwave-discharge lamp filtered with a vacuum UV (VUV) monochromator and detected by a solar-blind photomultiplier tube (PMT). A gas mixture of about 1% I_2 and H_2 diluted in He of 10 Torr is supplied in the microwave-discharge lamp. VUV light passes perpendicularly through the MgF_2 windows at 4 cm upstream of the end plate of the shock tube. In the measurement of I atoms, a solid iodine pellet cooled at 281 K is used to supply I_2 . Calibration curves for H and I atoms have been constructed by using decomposition of C_2H_5I ,

$$
C_2H_5I + M \rightarrow C_2H_5 + I + M
$$
 ($\phi = 0.90 \pm 0.05$)

and sequential decomposition of C_2H_5 ,

$$
\mathrm{C_2H_5}\rightarrow \mathrm{C_2H_4}+\mathrm{H}
$$

Attention has been paid in the optical alignment to keep the sensitivity to be optimized; detection limit of 10^{11} atom/cm³ for I and H atoms has been attained. In compensation for the achievement of high sensitivity, the resolution time of the detection is not sufficiently short for the measurements of very rapid reaction phenomena. By monitoring evolutions of I and H atoms in the thermal decomposition of C_2H_5I at 1900–2000 K and 2 atm, we measured the response time of the detection system to be about 25 μ s.

However, the reliability of the observed evolutions of the signal intensities can be sufficiently retained (except for the initial 25 μ s) if proper experimental conditions have been chosen; this is confirmed by analyzing evolutions of H atoms in the reaction of H + O_2 between 1700–2000 K in the mixtures of 0.2–0.4 ppm C₂H₅I + 300–500 ppm O₂.

The present experiment is conducted at very low concentration of sample mixtures, 0.1−0.4 ppm CH2I2 (and $+ 300$ ppm H₂) diluted in Ar so as to reduce the influence of the side reactions; however, the sample mixtures are prepared simply by the measurement of pressure by using combination of Baratron pressure gauges.

He (99.9995%, AGA Specialty Gases), Ar (99.9995%, AGA Specialty Gases), and H_2 (99.9995%, AGA Specialty Gases) are used without further purification. CH_2I_2 (99%, Sigma-Aldrich,

Reagent Plus grade) and C_2H_5I (99%, Sigma-Aldrich, Reagent Plus grade) are purified by repeating degassing by successive freezing and pumping cycles.

3. RESULTS AND DISCUSSIONS

3.1. Thermal Decomposition of $CH₂I₂$. Almost no kinetic information is available in the past literatures for $CH₂I₂$ decomposition. In the study on thermal decomposition of $CH₂I₂$, evolution of I atoms in the 0.1 ppm $CH₂I₂$ in Ar is monitored behind reflected shock waves over 1550−2010 K. Examples of the observed profile of [I] are demonstrated in Figure 1. As clearly shown, it is indicated that sequential two

Figure 1. [Examples of the observed evolution of I atoms in 0](http://pubs.acs.org/action/showImage?doi=10.1021/jp211849h&iName=master.img-001.jpg&w=184&h=334).1 ppm $CH_2I_2 + Ar: (A) T = 1556$ K, $P = 2.16$ atm, $[Ar] = 1.02 \times 10^{19} / \text{cm}^3$; (B) $T = 1761$ K, $P = 2.12$ atm, $[Ar] = 8.82 \times 10^{18} / \text{cm}^3$; (C) $T = 1848$ K, $P = 2.08$ atm, $[Ar] = 8.26 \times 10^{18} / \text{cm}^3$. Calculated profiles of I atoms by using eq III is shown by the dotted curve, where the initial rise is given for (A) by using $k_{1a} = 4.36 \times 10^{-9} \exp(-19858/T)/cm^3$ molecule⁻¹ s⁻¹ (the rate for thermal decomposition of CH₃I, which has nearly equal [diss](#page-2-0)ociation energy with reaction 1a), and the rise rate given by the response time of the detection system was used for (B) and (C) .

decomposition steps of C−I bond fissi[on](#page-0-0) dominate over other product channels because it is shown at high temperature that $[I]_{\infty}/[CH_2I_2]_0 = 2$ (where $[I]_{\infty}$ and $[CH_2I_2]_0$ denote the concentrations of final iodine atoms and initial $CH₂I₂$, respectively). Also, the first decomposition step, $CH₂I₂ + Ar \rightarrow CH₂I + I + Ar$ (1a) is found to be very fast, in comparison with the second step, $CH_2I + Ar \rightarrow {}^3CH_2 + I + Ar$ (1b), exhibiting that the reaction i[nte](#page-0-0)rmediate $CH₂I$ is stable even in the relatively high temperature range $(T > 1500 \text{ K})$.

For the sequential decomposition of $CH₂I₂$, the profile of concentration of I atoms is analytically given by

$$
\begin{aligned} \text{[I]} / [\text{CH}_2\text{I}_2]_0 &= \left[1 - \exp(-R_1 t)\right] + F_1 [1 - \exp(-R_1 t)] \\ &+ F_2 [1 - \exp(-R_2 t)] \end{aligned} \tag{I}
$$

where $R_1 = k_{1a}(Ar)$, $R_2 = k_{1b}(Ar)$, $F_1 = R_2/(R_2 - R_1)$, and $F_2 =$ $R_1/(R_1 - R_2)$. Because $R_1 \gg R_2$, the simple eq II is available in the analysis of the present experimental result,

$$
[1]/[CH_2I_2]_0 = [1 - \exp(-R_1t)] + [1 - \exp(-R_2t)]
$$

(II)

The observed initial rise rate of [I] is found to be too fast to evaluate k_{1a} in the temperature range above 1500 K. From the profile of I atoms in the range $1 < [I]/[CH_2I_2]_0 < 2$, the rate of (1b) was evaluated by using an estimated rate for R_1 into eq II^{28} and the result is summarized in Table 1 as well as in Figure 2. [Line](#page-0-0)ar least-squares analysis of the data on k_{1b} gives

Table 1. Summary of the Experimental Condition for Thermal Decomposition of $CH₂I₂$ and the Rate Constant k_{1b}

T/K	P/atm	$\left[\text{CH}_{2}\right]_{0}^{a}$	$[\text{Ar}]^b$	k_{1b}^{c}
1556	2.16	1.02	10.2	8.64×10^{-17}
1648	1.36	0.607	6.07	3.93×10^{-16}
1648	1.36	0.607	6.07	3.28×10^{-16}
1761	2.12	0.882	8.82	1.23×10^{-15}
1763	2.12	0.883	8.83	1.46×10^{-15}
1843	2.07	0.825	8.25	2.52×10^{-15}
1849	2.08	0.826	8.26	3.33×10^{-15}
1852	2.09	0.827	8.27	2.84×10^{-15}
1848	2.08	0.826	8.26	2.66×10^{-15}
2012	1.92	0.701	7.01	7.86×10^{-15}
2012	1.92	0.701	7.01	7.33×10^{-15}

 a In 10¹² molecule/cm³. b In 10¹⁸ atom/cm³. ^cIn the unit of cm³ moleccule $^{-1}$ s $^{-1}$.

Figure 2. Arrhenius plot of the reaction rate for CH₂I + Ar \rightarrow ³CH₂ + I + Ar (1b). Linear least-squares-analysis of the data is given by k_{1b}/cm^3 molecule⁻¹ s⁻¹ = 3.12 × 10⁻⁸ exp(−30170/T) and expressed by the st[raig](#page-0-0)ht solid line.

$$
\ln(k_{1b}/\text{cm}^3 \text{ molecule}^{-1} \text{s}^{-1})
$$

= -(17.28 ± 0.79) - (30.17 ± 1.40) × 10³/T (III)

over the temperature range $T = 1500-2000$ K.

The heat of reaction is estimated as $\Delta H^0_{\,\, 298} = 51.5$ kcal mol $^{-1}$ and $\Delta H^0_{\ 298} = 64.4$ kcal mol⁻¹ for (1a) and (1b), respectively, on the basis of the recent experimental data on the heat of formation of CH₂I and the C – H bond fission energy.²⁹ The heat of reaction for other possible 3-centered reactions such as $CH_2I_2 + M \to CHI + HI + M$, $CH_2I_2 + M \to {}^{1,3}CH_2 + I_2 + M$, and CH₂I + M \rightarrow CH + HI + M, is estimated as $\Delta H_{.298}^{0}$ = 72.5 kcal mol⁻¹, 79.1 kcal mol⁻¹ (for the spin-forbidden ³CH₂ formation), and 93.9 kcal mol⁻¹, respectively.^{30–33} Therefore, dominance of (1) over other channels, as well as two-steps production behavior of I atoms observed in t[his st](#page-5-0)udy can be justified thermo[d](#page-0-0)ynamically. The observed activation energy of 60 kcal/mol for (1b) seems to be consistent with the endothermicity of the reaction.

 $CH₂I₂$ is confirmed t[o be](#page-0-0) a clean and better source for supplying ${}^{3}CH_{2}$ than CH₂CO for the shock tube study below 2000 K; however, about 1800 K is indicated to be the lower limit for the purpose of quick supply. As (1b) is the rate determining step to produce ${}^{3}\mathrm{CH}_{2}$, result III is used as the production rate for ${}^{3}\mathrm{CH}_{2}$ in the analysis in the $CH_2 + H_2$ reaction in the following section. More detailed study on ther[mal](#page-0-0) decomposition of $CH₂I₂$ is now under way and will be presented elsewhere.³⁴

3.2. Reaction of CH₂ with H₂. Evolution of $[H]$ in the mixtures of [0](#page-5-0).2−0.4 ppm $CH₂I₂$ + 300 ppm $H₂$ in Ar is monitored over 1850−2040 K. In conducting an experiment with very low concentration of sample gas such as employed in this study, it is especially important to examine the validity of the prepared concentration of minor component, as well as to confirm that the reaction system is free from the effect of impurities: these requirements may not be generally so easy to achieve when the concentration of sample gas is extremely low. As described above, the validity of the nominal concentration of $CH₂I₂$ prepared by pressure measurement has been confirmed here (because the measured yield of I atoms is equal to 2 times of the nominal concentration of CH₂I₂ for $T > 1800$ K). In addition, measurement of [H] in the $CH₂I₂ +$ (excess H₂), as described below is useful to confirm this. These evidence ensure that the loss of $CH₂I₂$ should be negligible even for such low concentration samples.

The experimental condition of the present study is summarized in Table 2. All the data shown in the table are the averages

Table 2. Summary of the Experimental Conditions for CH_2 + H_2 Reaction and the Measured Rate Constants k_3 and k_{3max}

T/K	P/atm	$[Ar]^a$	$\left[\text{CH}_2\text{I}_2\right]_0^b$	$10^{10}k_3^{\ c}$	$10^{10}k_{3max}$			
0.4 ppm $CH_2I_2 + 300$ ppm $H_2 + Ar$								
2044	1.75	6.29	0.252	1.03 ± 0.33	2.14 ± 0.83			
1958	1.99	7.45	0.298	1.44 ± 0.20	2.31 ± 0.73			
1852	2.09	8.27	0.313	$1.15 + 0.31$	$2.16 + 0.18$			
0.2 ppm $CH2I2 + 300$ ppm $H2 + Ar$								
2041	1.86	6.69	0.134	$1.40 + 0.15$	$2.66 + 0.47$			
2002	1.88	6.9	0.138	1.36 ± 0.47	2.39 ± 0.93			
1938	2.01	7.62	0.152	$1.17 + 0.64$	$2.16 + 0.30$			
1902	2.01	7.77	0.155	$1.40 + 0.19$	2.21 ± 0.45			
1855	2.08	8.23	0.165	1.21 ± 0.55	$2.06 + 0.83$			
atom cm ⁻³ . ^b In 10 ¹³ molecule cm ⁻³ . ^c In the unit of cm ³ a In 10 ¹⁸ molecule ^{-1} s ^{-1} .								

of 2 data points conducted at the same shock wave condition; shot-by-shot fluctuation of the temperature shown in this table is less than \pm 5 K. Averaged values are shown for T and P. Repetition of the measurement at the same condition is useful to improve the S/N ratio (by signal averaging), as well as to confirm that reasonable reproducibility of the profiles of H atoms has been attained.

Also all the data shown in Table 2 are associated with blank tests using pure Ar and 300 ppm H_2 + Ar (both sample mixtures are prepared in the same c[on](#page-2-0)dition with the mixture of 0.2−0.4 ppm CH_2I_2 + 300 ppm H_2 + Ar) to confirm that H atom is not supplied by impurities in Ar, H_2 , nor the shock tube wall. Background H atom produced in the pure Ar sample was confirmed to be below the detection limit $(1 \times 10^{11} \text{ atom/cm}^3)$ in all the experimental conditions, but a small amount of H atom production is observed (up to 5 \times 10 $^{\rm 11}$ atom/cm $^{\rm 3)}$ in the 300 ppm H_2 + Ar mixture at the highest temperature of this study: this is not from the impurities but it can be attributed to thermal decomposition of H_2 ^{1,35}

$$
H_2 + Ar \to 2H + Ar \tag{6}
$$

An example of the observed profile of H atom produced in the mixtures of 0.2 ppm $CH₂I₂ + 300$ ppm $H₂$ is shown in Figure 3A.

Figure 3. [Example of the observed evolution of H atoms in the highly](http://pubs.acs.org/action/showImage?doi=10.1021/jp211849h&iName=master.img-003.jpg&w=238&h=255) diluted CH_2I_2 + 300 ppm H₂ in Ar and comparisons with simulations. (A) Experimental result shown by the black solid line. Sample gas: 0.2 ppm CH₂I₂ + 300 ppm H₂ in Ar, T = 2002 K, P = 1.88 atm, [Ar] = 6.90 \times 10¹⁸/cm³, [CH₂I₂]₀ = 1.38 \times 10¹²/cm³. Kinetic simulations using the mechanism of Table 2 are shown by the red solid curve and the values for $\pm 30\%$ of k_3 are shown by the red broken curves, respectively. The solution with the best fit of k_{3max} (maximum value for k_3 assuming $k_2 = 0$) is shown [by](#page-2-0) the black open circle. (B) Sensitivity coefficient (nondimension) for H atoms; S_{Hip} evaluated for the experimental condition of (A). The number indicated in this figure corresponds to the reaction number in the text and Table 3. The reactions in Table 3 not shown in this figure do not show any sensitivity.

Numerical si[mu](#page-4-0)lations have been conducted to anal[yze](#page-4-0) the reaction rates of (2) and (3), however, it is practically impossible to evaluate k_2 and k_3 independently, because the collisional energy transfer from ${}^{3}CH_{2}$ to ${}^{1}CH_{2}$ (-4) is very fast and quasi-equilibrium between the two electronic states of $CH₂$ is maintained; two kinds of analyses have been tried in this study to estimate k_3 by assuming the magnitude of k_2 , as described below.

The first approach of the analysis on k_3 here is to employ the result of theoretical calculation (ab initio molecular orbital and transition state theory, including Eckert correction) for the reaction (2) expressed as²⁷

$$
k_2
$$
/cm³ molecule⁻¹ s⁻¹ = 7.32 × 10⁻¹⁹T^{2.3} exp(-3699/T)
T = 200-3000 K (IV)

Using (IV) may be justified by the fact that (IV) agrees very well with the semiempirical data on k_2 based on the measurement of Gesser and Steacie¹² for the relative rate constant

Figure 4. [Summary of the reaction rates for](http://pubs.acs.org/action/showImage?doi=10.1021/jp211849h&iName=master.img-004.jpg&w=201&h=379) ³CH₂ + H₂ \rightarrow CH₃ + H (2) and ¹CH₂ + H₂ \rightarrow CH₃ + H (3). (A) k_2 (expressed by the black symbols): black solid line and black dashed line, TST calculation without Eckert correction and TST calculation with Eckert correction, r[es](#page-1-0)pe[ct](#page-1-0)ively (ref 26); Δ connected by the black broken line, semiempirical result obtained by the relative measurement of k_2 combined with TST/quantum chemical calculation (refs 12 and 26); ■, ref 13; ◆, ref 1[4;](#page-5-0) [d](#page-5-0)otted line, ref 16; \times and +, ref 25. k_3 (expressed by the red symbols): red circle, present study; red solid line and red dashed line, [re](#page-5-0)f 25 $(k_2 + k_3)$; red dashed-dotted line, [ref 1](#page-5-0)7[;](#page-5-0) red da[she](#page-5-0)d line, r[ef](#page-5-0) [1](#page-5-0)8; red s[qua](#page-5-0)re, ref 20; red tri[ang](#page-5-0)le, ref 21. (B) k_2 (expressed by the black symbols): black solid line and black dashed line, TST calculation wit[hou](#page-5-0)t Eckert correction and with Eck[ert](#page-5-0) correction, respecti[vel](#page-5-0)y ([re](#page-5-0)f 21); \times an[d](#page-5-0) [+](#page-5-0) with dotted line[,](#page-5-0) ref 25. k_3 (expressed by the red symbols): red circle, present study for k_3 ; red triangle, present study for the maximum value for k_3 , i.e., k_{3max} (see text); red solid line, ref 25 $(k_2 + k_3)$, [wh](#page-5-0)ere the upper and lower limits [of](#page-5-0) ref 25 are shown by the red dashed lines; red dotted line, extrapolation of the low te[mpe](#page-5-0)rature study of ref 17.

Table 3. Reaction Mechanism for Analyzing the Observed Profile of the H Atom

"Forward and reverse reactions are considered when connected by "=". ${}^b k = AT^n \exp(-E_a/RT)$ [molecule, cm³, K, cal]. "Thir[d-](#page-5-0)body collision efficiency for M $(=Ar)$ [i](#page-5-0)s taken from ref 1. ^dOnly parameters for the high pressure limit are shown but the rate for the falloff region is evaluated by using parameters given in ref 1.

for the reaction of ³CH₂ [wit](#page-5-0)h H₂ ([2\)](#page-5-0) against

$$
{}^{3}CH_{2} + CH_{2}CO \rightarrow {}^{3}C_{2}H_{4} + CO \qquad \text{(reference reaction)}
$$

combined with computed rate constant for ${}^{3}CH_{2} + CH_{2}CO^{27}$ for the temperature range 230−370 K.

By using a reaction scheme shown in Table 3, we co[n](#page-5-0)ducted fitting the numerical simulation to the observed profile for the evolution of H atoms in the range of initial fast rise for $t = 25-150 \mu s$, where the profile of H atoms is sensitive to the reactions ${}^{3}CH_{2} + H_{2} \rightarrow CH_{3} + H (2)$ and ${}^{1}CH + H \rightarrow CH + H (3)$. The optimized solutions for k ${}^{1}CH_{2} + H_{2} \rightarrow CH_{3} + H$ (3). The optimized solutions for k_{3} , which give the best fit to the experimental profil[es](#page-1-0), are summarized in Table 2, [an](#page-1-0)d an example is shown by the red solid curve in Figure 3A.

The second approa[ch](#page-2-0) of the present analysis is the limiting case evaluating the u[pp](#page-3-0)er limit of k_3 , i.e., $k_{3\text{max}}$ with an assumption $k_2 = 0$. As shown by the black circle in Figure 3A, it is possible to achieve good agreement of the numerical simulation to the experimental profile of H atoms even for neglec[tin](#page-3-0)g the contribution of (2). The results of the analyses on k_{3max} are summarized also in Table 2.

An example o[f t](#page-1-0)he computed sensitivity coefficients (nondimensional) are shown i[n](#page-2-0) Figure 3B. Contributions of the reactions in Table 3 other than $(1)–(6)$ are in fact negligibly small, as the concentration of CH_2I_2 used in this study is very low. Contribution for the delay [o](#page-0-0)[f](#page-3-0) [pr](#page-3-0)oducing ${}^{3}CH_{2}$ in the thermal decomposition of $CH₂I₂$ (1) is significant at the initial stage of the reaction, $CH_3 + H_2 \rightarrow CH_4 + H_2$ (5) dominates for large t , and the reaction (6) has some sensitivity at high temperature range, $T > 2000$ K, nevertheless, it is demonstrated that (2) and (3) are sufficien[tly](#page-3-0) sensitive to evaluate kinetic rate constant. It is also worthwhile to mention that the numerical simulation can reproduce very well the observed profile of H atoms with using the nominal value of the initial concentration of CH_2I_2 for all the experimental data; computation to estimate the accuracy for $[CH₂I₂]₀$ has been also performed and the nominal value is concluded to be reliable with $\pm 10\%$ error limit.

The present experimental result for (3) by employing theoretical result for k_2 can be expressed as

$$
k_3
$$
/cm³ molecule⁻¹ s⁻¹ = (1.27 ± 0.36) × 10⁻¹⁰ (V)

and the upper limit of k_3 (k_{3max}) by assuming $k_2 = 0$ can be expressed as

$$
k_{3\text{max}}/\text{cm}^3
$$
 molecule⁻¹ s⁻¹ = (2.26 ± 0.59) × 10⁻¹⁰ (VI)

for the temperature range of $T = 1850-2050$ K, here, the error limit is given by 2σ .

The result of the present study on $k₃$ is compared with previous works on k_2 and k_3 in Figure 4A (summary of the data for a wide temperature range), and in Figure 4B (high temperature data including $k_{3\text{max}}$).

As shown in Figure 4A,B, the r[ate](#page-3-0) for (3[\)](#page-3-0) evaluated in this study is found to agree very well with that of previous shock tube work, 15 as [we](#page-3-0)ll as with the exp[er](#page-1-0)imental works below 1000 K. $17-20$ Agreement of the high temperature data on k_3 with the expe[rim](#page-5-0)ental result by Gannon et al. conducted between 195−[798](#page-5-0) K¹⁷ implies that k_3 shows almost no temperature dependence. Although the result by Friedrichs and Wagner²⁵ was indicat[ed](#page-5-0) to be $k_2 + k_3$, it should be approximately equal to k_3 , because the contribution of k_2 is indicated to be minor. Their estimated upper limit for $k_2 + k_3$ also agrees very well with k_{3max} of this study.

As for reaction (2), it is difficult to examine k_2 precisely only from the present experimental information. The results on k_2 evaluated by Friedr[ic](#page-1-0)hs and Wagner²⁵ are also shown in Figure 4, but it seems difficult to extract a reliable estimate because it should be very sensitive to the uncertainty of the magnitude [of](#page-3-0) measured $k₃$.

The main conclusion of this study, in agreement with Friedrichs and Wagner,²⁵ is that the importance of ${}^{1}CH_{2}$ in the reaction of $CH_2 + H_2$ has been confirmed; i.e., the reaction at elevated temperature can proceed through collisional excitation from ${}^{3}CH_{2}$ to ${}^{1}CH_{2}$ if the reaction rate of ${}^{3}CH_{2}$ is not extremely large. The same scenario may hold for the reactions of $CH₂$ with other molecules. Gannon et al.¹⁷ demonstrated in the study of ${}^{1}CH_{2} + D_{2}$ reaction that an insertion reaction can be competitive to the direct abstraction reaction, because they confirmed that two-thirds of the products of this reaction was H atom. For the molecules other than $H₂$, insertion reaction can still be a part of the main channels for the thermal reactions of CH₂ at elevated temperature. Examination of the relative contributions of ${}^{3}CH_{2}$ and ${}^{1}CH_{2}$ in many of the key reactions in combustion system seems to be still a challenging task.

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